

ABSTRACT

5 Provided is a reflective mask blank for manufacturing a reflective mask capable of forming a transfer pattern of diversified fine pattern shapes formed on a transferred substrate and having a transfer pattern capable of performing EUV exposure with a high throughput

10 A reflective mask blank comprises a multilayer reflective film and an absorber film in this order on a substrate. When normalization is performed with a value of an evaluation function of a film having a refractive index of 0.95 and an extinction coefficient of 0.03 as 1, the absorber film comprises a material having such a refractive index and an extinction coefficient that a value of the normalized evaluation function of the absorber film is 1.015 or more, and the evaluation function is a product of a normalized image log slope (NILS) and a threshold of light intensity for exposure of a predetermined resist to light.

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